

Ken Cadien

List of Publications by Year in descending order

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Version: 2024-02-01

61
papers

1,124
citations

361045

20
h-index

433756

31
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all docs

62
docs citations

62
times ranked

1472
citing authors

#	ARTICLE	IF	CITATIONS
1	Interaction Mechanisms between Air Bubble and Molybdenite Surface: Impact of Solution Salinity and Polymer Adsorption. <i>Langmuir</i> , 2017, 33, 2353-2361.	1.6	67
2	Adsorption characteristics and mechanisms of O-Carboxymethyl chitosan on chalcopyrite and molybdenite. <i>Journal of Colloid and Interface Science</i> , 2019, 552, 659-670.	5.0	65
3	Comparing XPS on bare and capped ZrN films grown by plasma enhanced ALD: Effect of ambient oxidation. <i>Applied Surface Science</i> , 2018, 435, 367-376.	3.1	57
4	Observation of long-range dipole-dipole interactions in hyperbolic metamaterials. <i>Science Advances</i> , 2018, 4, eaar5278.	4.7	57
5	Freestanding hierarchical porous carbon film derived from hybrid nanocellulose for high-power supercapacitors. <i>Nano Research</i> , 2017, 10, 1847-1860.	5.8	55
6	Selective flotation separation of molybdenite and talc by humic substances. <i>Minerals Engineering</i> , 2018, 117, 34-41.	1.8	46
7	Growth mechanism of atomic layer deposition of zinc oxide: A density functional theory approach. <i>Applied Physics Letters</i> , 2013, 103, .	1.5	40
8	Advances in Characterization of CMP Consumables. <i>MRS Bulletin</i> , 2002, 27, 766-771.	1.7	38
9	A route to low temperature growth of single crystal GaN on sapphire. <i>Journal of Materials Chemistry C</i> , 2015, 3, 7428-7436.	2.7	38
10	Ultra low density of interfacial traps with mixed thermal and plasma enhanced ALD of high- ϵ^p gate dielectrics. <i>RSC Advances</i> , 2016, 6, 16301-16307.	1.7	38
11	Achieving ultrahigh corrosion resistance and conductive zirconium oxynitride coating on metal bipolar plates by plasma enhanced atomic layer deposition. <i>Journal of Power Sources</i> , 2018, 397, 32-36.	4.0	37
12	Growth, structure and properties of sputtered niobium oxide thin films. <i>Thin Solid Films</i> , 2011, 519, 3068-3073.	0.8	35
13	Flotation separation of Cu-Mo sulfides by O-Carboxymethyl chitosan. <i>Minerals Engineering</i> , 2019, 134, 202-205.	1.8	35
14	Separation of talc and molybdenite: challenges and opportunities. <i>Minerals Engineering</i> , 2019, 143, 105923.	1.8	34
15	Selective separation of copper-molybdenum sulfides using humic acids. <i>Minerals Engineering</i> , 2019, 133, 43-46.	1.8	33
16	Carbon nanosheets derived from reconstructed lignin for potassium and sodium storage with low voltage hysteresis. <i>Nano Research</i> , 2021, 14, 4664-4673.	5.8	24
17	Al_2O_3 pulsed atomic layer deposition: Numerical growth model and experiments. <i>Journal of Applied Physics</i> , 2016, 119, .	1.1	23
18	Low Thermal Budget Heteroepitaxial Gallium Oxide Thin Films Enabled by Atomic Layer Deposition. <i>ACS Applied Materials & Interfaces</i> , 2020, 12, 44225-44237.	4.0	23

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19	Chemically enhanced synergistic wear: A copper chemical mechanical polishing case study. <i>Wear</i> , 2013, 307, 155-163.	1.5	22
20	Electrical Comparison of HfO_2 and ZrO_2 Gate Dielectrics on GaN. <i>IEEE Transactions on Electron Devices</i> , 2013, 60, 4119-4124.	1.6	21
21	Probing initial-stages of ALD growth with dynamic in situ spectroscopic ellipsometry. <i>Applied Surface Science</i> , 2015, 328, 344-348.	3.1	21
22	Surface reaction kinetics in atomic layer deposition: An analytical model and experiments. <i>Journal of Applied Physics</i> , 2018, 124, .	1.1	20
23	$\text{Zr}_2\text{N}_2\text{O}$ Coating-Improved Corrosion Resistance for the Anodic Dissolution Induced by Cathodic Transient Potential. <i>ACS Applied Materials & Interfaces</i> , 2018, 10, 40111-40124.	4.0	19
24	Low temperature plasma enhanced atomic layer deposition of conducting zirconium nitride films using tetrakis (dimethylamido) zirconium and forming gas (5% H_2 + 95% N_2) plasma. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2015, 33, .	0.9	18
25	Sustained hole inversion layer in a wide-bandgap metal-oxide semiconductor with enhanced tunnel current. <i>Nature Communications</i> , 2016, 7, 10632.	5.8	16
26	The effect of argon pressure, residual oxygen and exposure to air on the electrical and microstructural properties of sputtered chromium thin films. <i>Thin Solid Films</i> , 2012, 520, 1762-1767.	0.8	15
27	Plasma enhanced atomic layer deposition of ZnO with diethyl zinc and oxygen plasma: Effect of precursor decomposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2016, 34, .	0.9	15
28	Growth and Characterization of Metastable Hexagonal Nickel Thin Films via Plasma-Enhanced Atomic Layer Deposition. <i>ACS Applied Materials & Interfaces</i> , 2017, 9, 24722-24730.	4.0	15
29	Schottky barrier source-gated ZnO thin film transistors by low temperature atomic layer deposition. <i>Applied Physics Letters</i> , 2013, 103, .	1.5	14
30	Understanding the Effects of a High Surface Area Nanostructured Indium Tin Oxide Electrode on Organic Solar Cell Performance. <i>ACS Applied Materials & Interfaces</i> , 2017, 9, 38706-38715.	4.0	14
31	Challenges for on-chip optical interconnects. , 2005, 5730, 133.		13
32	Atomic Layer Deposition. , 2018, , 359-377.		13
33	In Situ Spectroscopic Ellipsometry Study of Plasma-Enhanced ALD of Al_2O_3 on Chromium Substrates. <i>Journal of the Electrochemical Society</i> , 2011, 159, D59-D64.	1.3	12
34	Capacitance Modeling and Characterization of Planar MOSCAP Devices for Wideband-Gap Semiconductors With High- κ Dielectrics. <i>IEEE Transactions on Electron Devices</i> , 2012, 59, 2662-2666.	1.6	11
35	Interfacial Contact Effects in Top Gated Zinc Oxide Thin Film Transistors Grown by Atomic Layer Deposition. <i>IEEE Transactions on Electron Devices</i> , 2016, 63, 3540-3546.	1.6	11
36	$\text{Hf}_{1-x}\text{Zr}_x\text{O}_2$ and $\text{HfO}_2/\text{ZrO}_2$ gate dielectrics with extremely low density of interfacial defects using low temperature atomic layer deposition on GaN and InP. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2021, 39, .	0.9	11

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37	Influence of atomic layer deposition valve temperature on ZrN plasma enhanced atomic layer deposition growth. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2015, 33, .	0.9	9
38	Evaluation of efficiency factors and internal resistance of thermoelectric materials. <i>International Journal of Energy Research</i> , 2017, 41, 198-206.	2.2	9
39	Transient Potential Induced Anodic Dissolution of 316L Stainless Steel in Sulfuric Acid Solution. <i>Journal of the Electrochemical Society</i> , 2019, 166, C3355-C3363.	1.3	8
40	Xâ€Ray Spectromicroscopy Investigation of Heterogeneous Sodiation in Hard Carbon Nanosheets with Vertically Oriented (002) Planes. <i>Small</i> , 2021, 17, e2102109.	5.2	8
41	TiO ₂ -HfN Radial Nano-Heterojunction: A Hot Carrier Photoanode for Sunlight-Driven Water-Splitting. <i>Catalysts</i> , 2021, 11, 1374.	1.6	8
42	High-mobility solution-processed zinc oxide thin films on silicon nitride. <i>Physica Status Solidi - Rapid Research Letters</i> , 2014, 8, 871-875.	1.2	7
43	Atomic layer deposition of iron oxide on a porous carbon substrate via ethylferrocene and an oxygen plasma. <i>Surface and Coatings Technology</i> , 2021, 421, 127390.	2.2	6
44	Solar wafer emitter measurement by infrared reflectometry for process control: Implementation and results. , 2014, , .		5
45	Electrical Characteristics of TiW/ZnO Schottky contact with ALD and PLD. <i>Materials Research Society Symposia Proceedings</i> , 2014, 1635, 127-132.	0.1	5
46	Defect Characterization of PEALD High-k ZrO ₂ Films Fabricated on IIIâ€V Materials. <i>IEEE Transactions on Semiconductor Manufacturing</i> , 2016, 29, 355-362.	1.4	5
47	Tetraallyltin precursor for plasma enhanced atomic layer deposition of tin oxide: Growth study and material characterization. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019, 37, .	0.9	5
48	Ceria coated silica particles: One step preparation and settling behaviour under the influence of colloidal and hydrodynamic interactions. <i>Materials Chemistry and Physics</i> , 2016, 173, 467-474.	2.0	4
49	In Situ Synchrotron Xâ€Ray Diffraction Analysis of Phase Transformation in Epitaxial Metastable hcp Nickel Thin Films, Prepared via Plasmaâ€Enhanced Atomic Layer Deposition. <i>Advanced Materials Interfaces</i> , 2018, 5, 1800957.	1.9	4
50	ZnO Schottky Nanodiodes Processed From Plasma-Enhanced Atomic Layer Deposition at Near Room Temperature. <i>IEEE Transactions on Electron Devices</i> , 2018, 65, 4513-4519.	1.6	3
51	Chemical Mechanical Polishing. , 2001, , 501-512.		2
52	CMP Method and Practice. , 2012, , 179-219.		2
53	Conformal Carbon Nanotube Coatings for Ceramic Composite Structures. <i>MRS Advances</i> , 2017, 2, 1499-1503.	0.5	2
54	AlN PEALD with TMA and forming gas: study of plasma reaction mechanisms. <i>RSC Advances</i> , 2021, 11, 12235-12248.	1.7	2

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55	High ionic conductivity of ultralow yttria concentration yttria-stabilized zirconia thin films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2022, 40, 042405.	0.9	2
56	Chemical mechanical polishing of boron-doped polycrystalline silicon. Proceedings of SPIE, 2014, , .	0.8	1
57	Stoichiometry controlled homogeneous ternary oxide growth in showerhead atomic layer deposition reactor and application for $Zr_xHf_{1-x}O_2$. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2021, 39, 030401.	0.9	1
58	On-Chip Power Generation: Microfluidic-Based Reactor for Catalytic Combustion of Methanol. , 2013, , .		0
59	Optimization of Copper Schottky Contacts on Nanocrystalline ZnO thin films by Atomic Layer Deposition. MRS Advances, 2016, 1, 3421-3427.	0.5	0
60	Resolving self-limiting growth in silicon nitride plasma enhanced atomic layer deposition with tris-dimethylamino silane precursor. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38, 062406.	0.9	0
61	From Amorphous to β -Gallium Oxide: Practical Implementation of Energetics Considerations in Process Design and Optimization. ECS Meeting Abstracts, 2021, MA2021-01, 2104-2104.	0.0	0